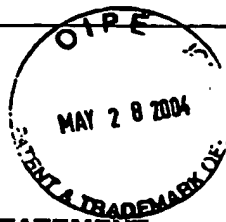


FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
	306640	P-0390.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: DIERICHS et al.	
Appln. No.: 10/719,009	
Filing Date: November 24, 2003	
Examiner: NOT ASSIGNED	Group Art Unit: 2874

Date: May 28, 2004

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
JM	AR	5,257,132	10/1993	Ceglio et al.			
	BR						
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						
	OR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	PR								
	QR								
	RR								
	SR								
	TR								
	UR								
	VR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

	WR								
	XR								
	YR								
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	BBR								
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Applicant: DIERICHS et al.

Appln. No.: TO BE ASSIGNED

Filing Date: November 24, 2003

Date: November 24, 2003

Page

1

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1

Examiner:

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
JM	AR	5,328,784	07/1994	FUKUDA			
JM	BR	6,007,888	12/1999	KIME			
JM	CR	6,375,870	04/2002	VISOVSKY et al.			
JM	DR	6,392,792	05/2002	NAULLEAU			
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						
	OR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	Abstract		Readily Available	
						Enclosed	No	Enclose	No
JM	PR	2001-100018	04/2001	JAPAN	MAEHARA HIROSHI	X			
	QR								
	RR								
	SR								
	TR								
	UR								
	VR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

JM	WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," <i>J. Vac. Sci. Technol. B</i> 12(6):3833-3840, XP-002096163 (1994)			
	XR				
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

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